

0160-0193-0 PCT

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF:

HIROSHI IKEDA ET AL

: ATTN: APPLICATION DIVISION

SERIAL NO: 09/463,961

:

5/14

FILED: February 10, 2000

:

D.G.

FOR: PROCESS AND APPARATUS FOR
TREATING SEMICONDUCTOR
PRODUCTION EXHAUST GASES

8-24-00

PRELIMINARY AMENDMENT

ASSISTANT COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

SIR:

Prior to examination on the merits, please amend the above-identified application as follows.

IN THE CLAIMS

Please amend the claims as follows.

Claim 5, lines 1-2, replace "any one of Claims 1 to 4" with --Claim 1--.

Claim 6, lines 1-2, replace "any one of the Claims 1 to 5" with --Claim 1--.

Claim 7, lines 1-2, replace "any one of Claims 1 to 7" with --Claim 1--.

Finally (e) mm